

In The Specification:

Please replace paragraph [0050] as follows:

[0050] The pattern formed in the amorphous carbon layer 130 may then be transferred to the conductive material layer 120 and any intervening layer by etching using an appropriate chemical etchant to form conductive material features 160 as shown in Figure [[1D]] 1C. Any known conductive material etchant may be used to etch the conductive material 120.